

Applicants hereby provisionally elect the Group III claims with traverse. Applicants respectfully submit that the Restriction Requirement is improper for the following reasons.

Since the four groups of claims relate to circuits or circuit elements that are made using aperture masks, the searches required will be substantially the same for each group. A search for the deposition method should also produce references concerning the deposition system, and integrated circuits and transistors made using aperture mask deposition techniques. Searching the four groups for a single patent application thus should not present an extra burden for the PTO.

Even if the Restriction Requirement is maintained, Applicants believe that Groups I, III, and IV should be combined into one group since they are all classified in the same class (Class 257). At a minimum, Applicants believe that Groups III and IV should be combined into one group since integrated circuits often comprise transistors linked together by electrical connections. A search for circuits made using aperture mask deposition should also produce references concerning circuit elements made using aperture mask deposition. Applicants therefore respectfully request reconsideration (and withdrawal or at least modification) of the Restriction Requirement.

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Respectfully submitted,

By

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